

INFORMATION DISCLOSURE CITATION IN AN APPLICATION

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 APPLICANT
Xuelong SHI, et al.

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 GROUP
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U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
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	5,242,770	9/7/1993	Chen et al.	430	5	
	5,296,891	3/22/1994	Vogt et al.	355	67	
	5,523,193	6/4/1996	Nelson	430	311	
	5,969,441	10/19/1999	Loopstra et al.	310	12	
	6,046,792	4/4/2000	Van Der Werf et al.	355	53	

FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
W	WO 98/40791	9/17/1998	WIPO (PCT/IB98/00254) ABSTRACT			<input checked="" type="checkbox"/>	

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

W	E. Wolf, "Electromagnetic diffraction inoptical systems, I. An integral representation of the image field", Department of Theoretical Physics, University of Manchester, pp. 349-356, <i>dated 1959</i> .
	Michael S. Yeung et al., "Extension of the Hopkins theory of partially coherent imaging to include thin-film interference effects, SPIE Vol. 1927 Optical/Laser Microlithography VI (1993), pp. 452-463.
W	Donis G. Flagello et al., "Theory of high-NA imaging in homogeneous thin films", 1996 Optical Society of America, pp. 53-64.
	J. Fung Chen et al., "An OPC Technology Roadmap to 0.14 μ m Design Rules", SPIE Vol. 3236, pp. 382-396. <i>no date</i>
W	Robert Socha et al., "Forbidden Pitches for 130nm lithography and below", Proceedings of SPIE Vol. 4000 (2000), pp. 1140-4455.

 EXAMINER **W. S. H.**

 DATE CONSIDERED **10/2003**